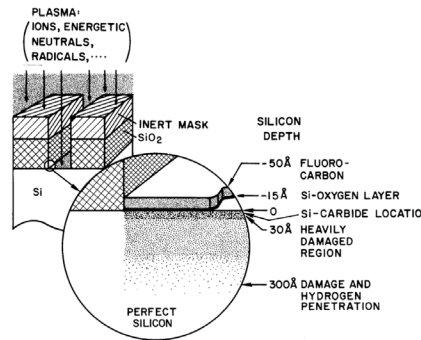
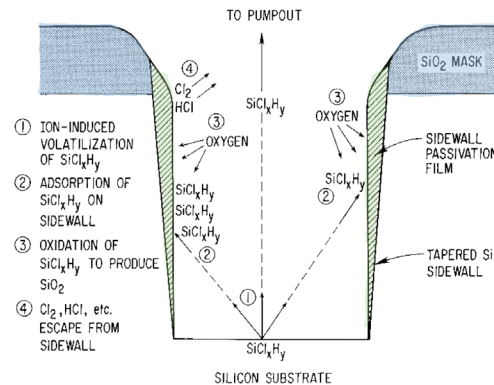


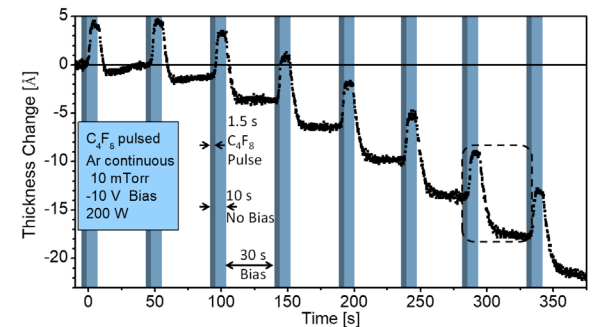
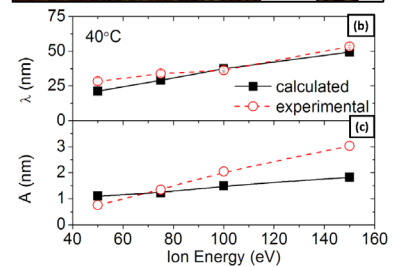
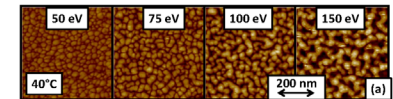
The 3rd Plasma Materials Science Hall of Fame Prize

was awarded to
Prof. Gottlieb S. Oehrlein,
University of Maryland,

for the excellent achievements in fundamental research on non-equilibrium physicochemical reactions at the interfaces between plasma and materials during plasma etching for microelectronics manufacturing, which have led plasma materials science for many years as a guiding principle for the research and development of ultra-fine processing technology.



Diagnostics and Clarification of Plasma-Surface Interactions



Atomic Layer Etching